

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

DIERICHS et al.

Application No.: TO BE ASSIGNED

Group Art Unit: UNKNOWN

Filed: November 24, 2003

Examiner: UNKNOWN

Title: METHOD OF FABRICATING AN OPTICAL ELEMENT, LITHOGRAPHIC APPARATUS AND DEVICE MANUFACTURING METHOD

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November 24, 2003

INFORMATION DISCLOSURE STATEMENT

MAIL STOP PATENT APPLICATION
Commissioner for Patents
P.O. BOX 1450
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 CFR 1.56, the attention of the Patent and Trademark Office is hereby directed to the references listed on the attached PTO-1449. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the references be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

The undersigned respectfully notes that copies of U.S. references are not required in applications filed after June 30, 2003.

This Information Disclosure Statement is being filed (a) within three months of the U.S. filing date of this non-CPA application, OR (b) before the mailing date of the first Office Action on the merits in the present application. No certification or fee is required.

The references were cited in a counterpart foreign application. An English language version of the foreign search report is attached for the Examiner's information.

Respectfully submitted,

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FORM PTO-1449 (modified)
 To: U.S. Department of Commerce
 (PW FORM PAT-1449)
 Patent and Trademark Office

Atty. Dkt. No.	M#	Client Ref.
	306640	P-0390.010-US

**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Date: November 24, 2003

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Applicant: DIERICHS et al.

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U.S. PATENT DOCUMENTS

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
AR	5,328,784	07/1994	FUKUDA			
BR	6,007,888	12/1999	KIME			
CR	6,375,870	04/2002	VISOVSKY et al.			
DR	6,392,792	05/2002	NAULLEAU			
ER						
FR						
GR						
HR						
IR						
JR						
KR						
LR						
MR						
NR						
OR						

FOREIGN PATENT DOCUMENTS

	Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
					Enclosed	No	Enclose	No
PR	2001-100018	04/2001	JAPAN	MAEHARA HIROSHI	X			
QR								
RR								
SR								
TR								
UR								
VR								

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

WR	Nguyen et al., "Imaging of extreme ultraviolet lithographic masks with programmed substrate defects," <i>J. Vac. Sci. Technol. B</i> 12(6):3833-3840, XP-002096163 (1994)			
XR				
YR				
ZR				
AAR				
BBR				
CCR				

Examiner

Date Considered:

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.